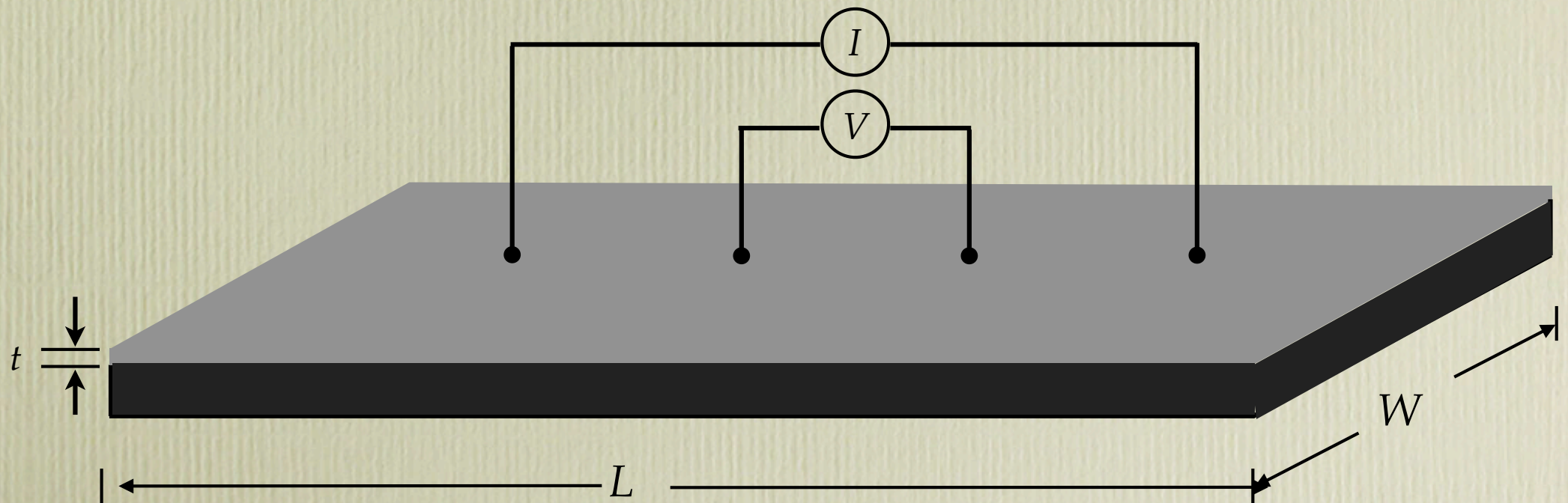


# Resistance

- Changes in all material properties affect resistance
  - Composition
  - Temperature
  - Hydrogen uptake
  - Strain
  - Exposure to light
  - Oxidation
- Often used as a monitoring method



# Resistance measurements





# Resistance measurements

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  - Temperature
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# Resistance measurements

- Changes in all material properties affect resistance
  - Composition
  - Temperature
  - Hydrogen uptake
  - Strain
  - Exposure to light
  - Oxidation
  - thickness

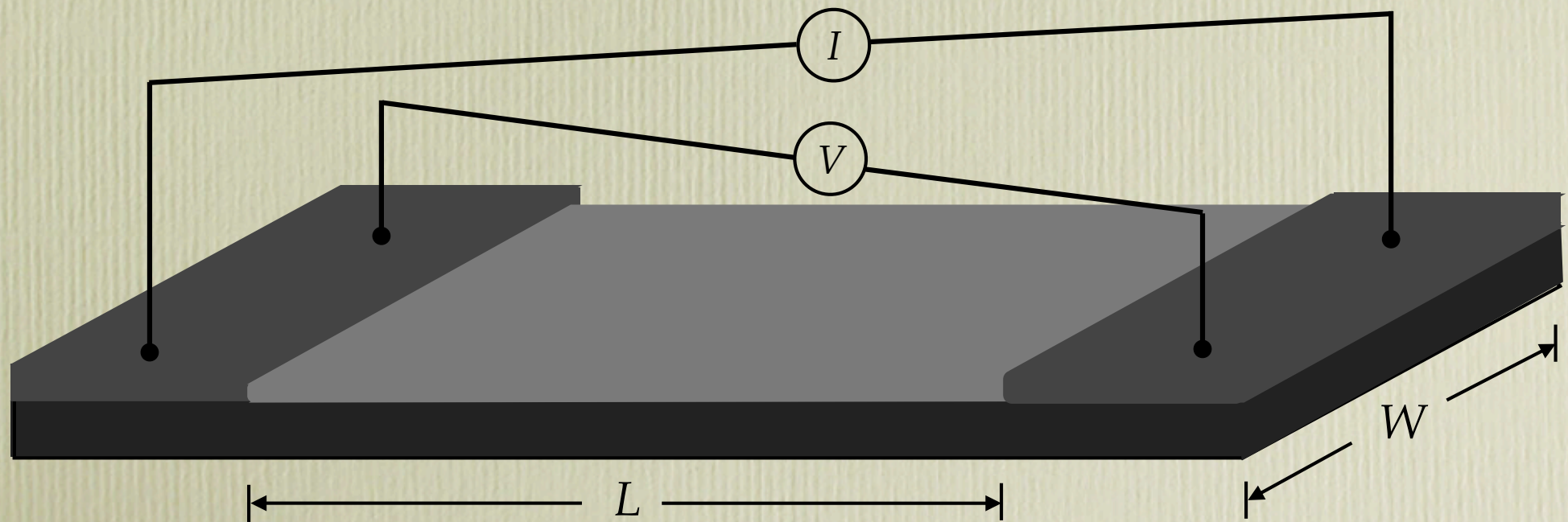


# Resistance measurements

- Changes in resistance with thickness
  - Surface scattering
  - Grain boundary scattering
- At what nominal thickness does the film start to conduct?
- At what nominal thickness does the film become continuous?
- Can we use the resistance measurements to obtain information during growth and after

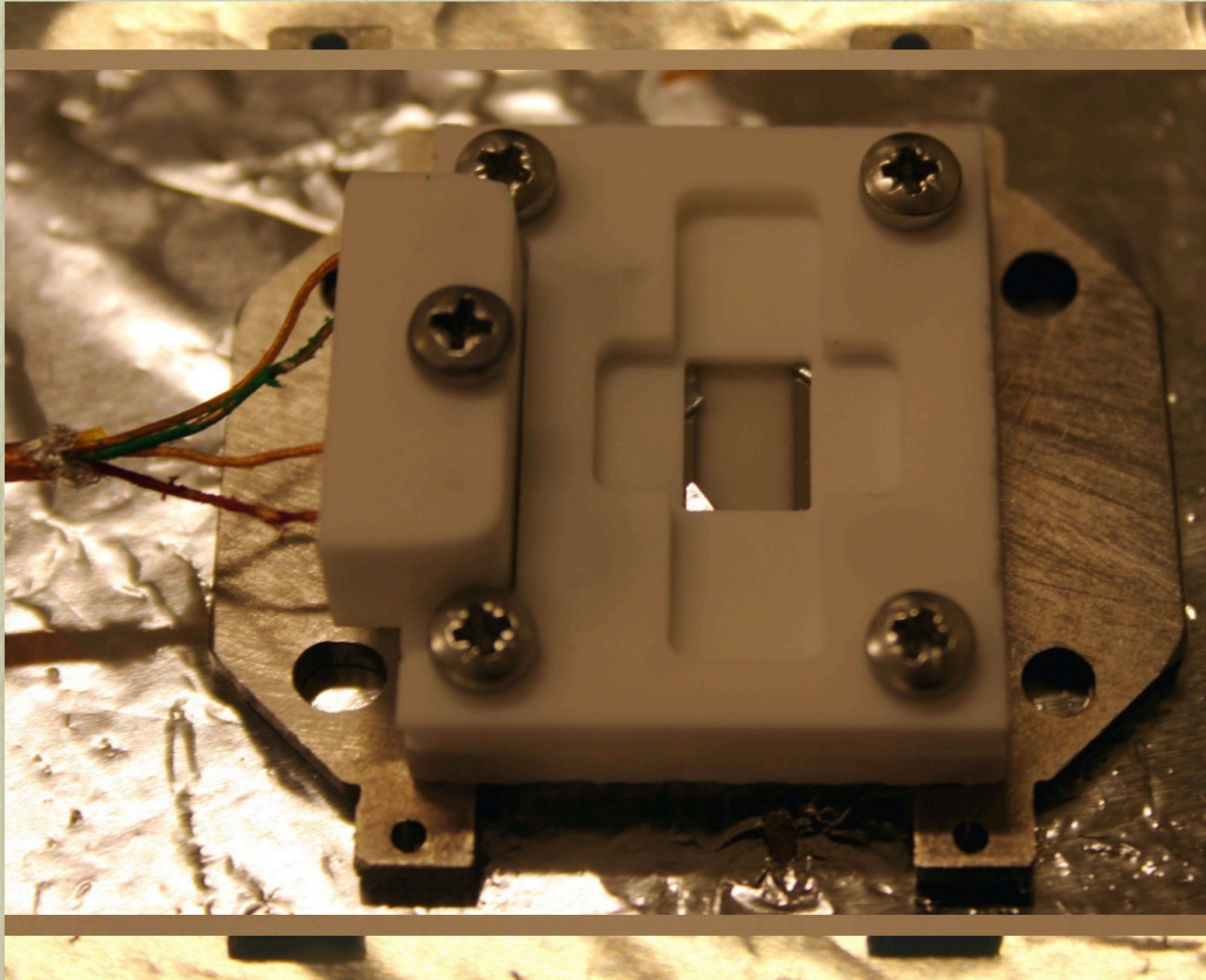


# Resistance measurements in situ





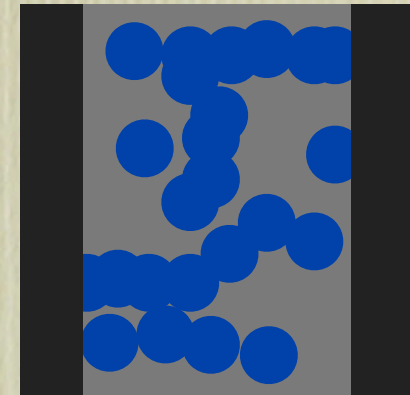
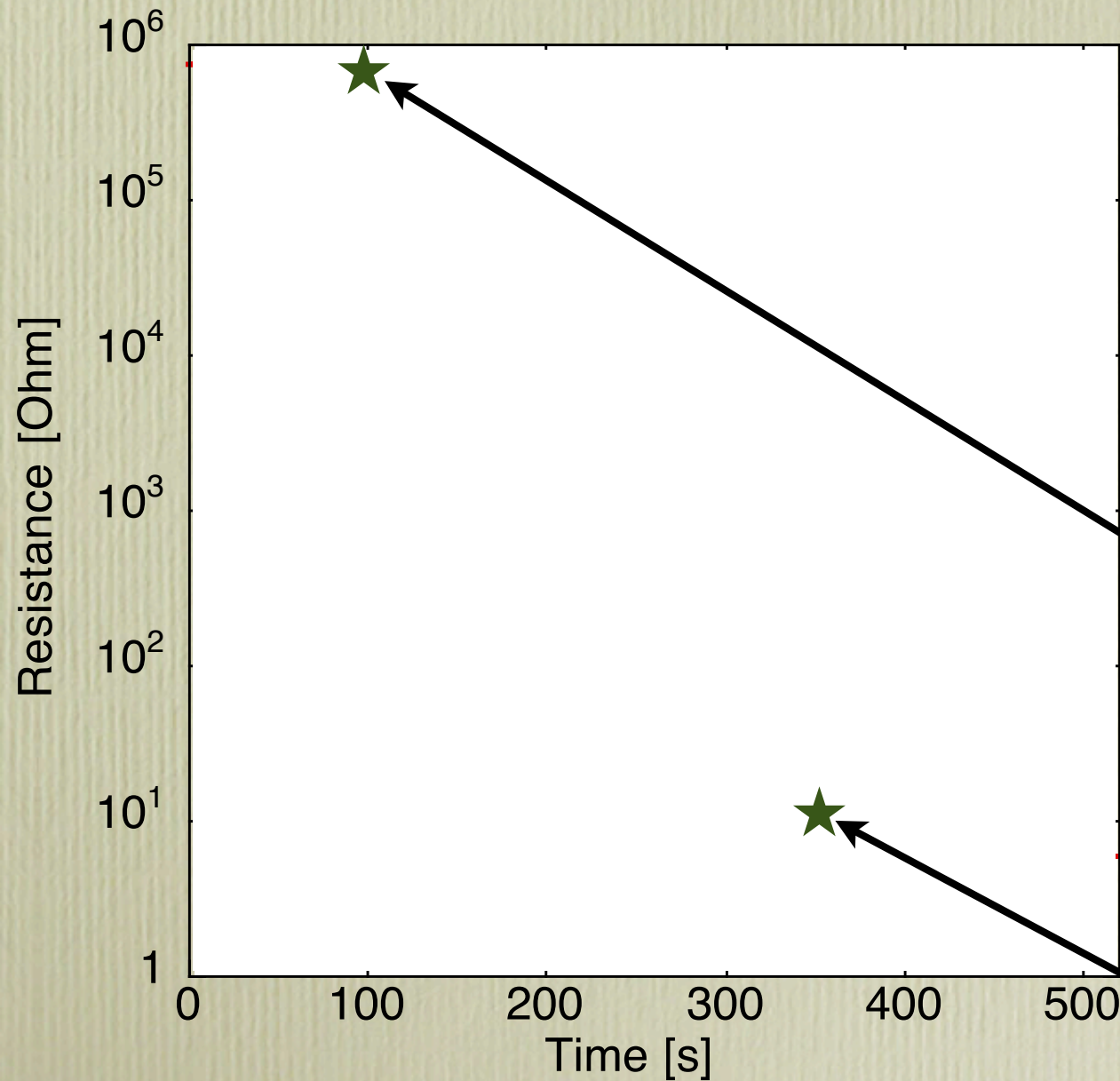
# Measurement setup



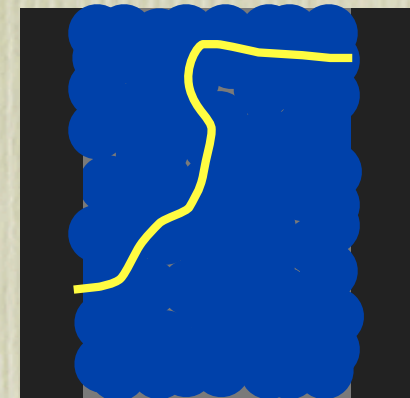


# Resistance during growth

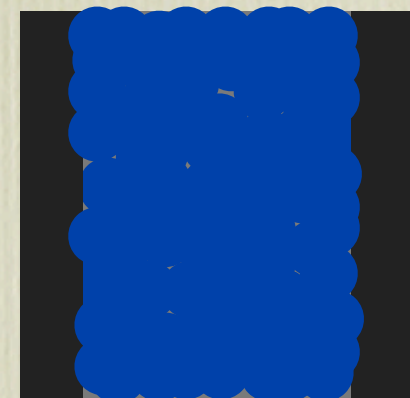
Pd on MgO at 200 °C



Discrete islands



Coalescence thickness



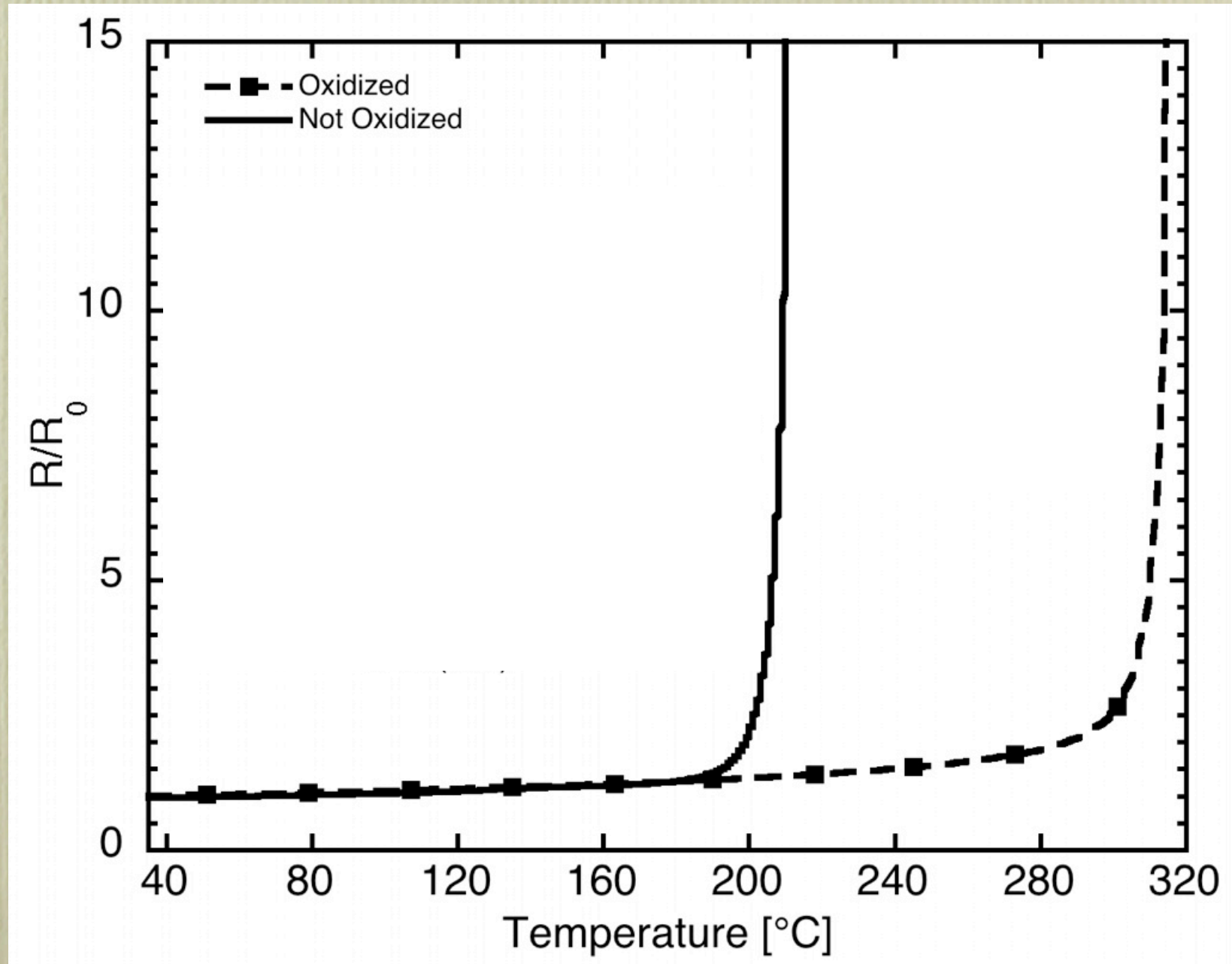
Continuity thickness



What about evaporation and  
oxidation?



# Evaporation of oxidized and not oxidized Mg





# Hydrogen in magnesium, absorption and desorption

300-400 °C!!

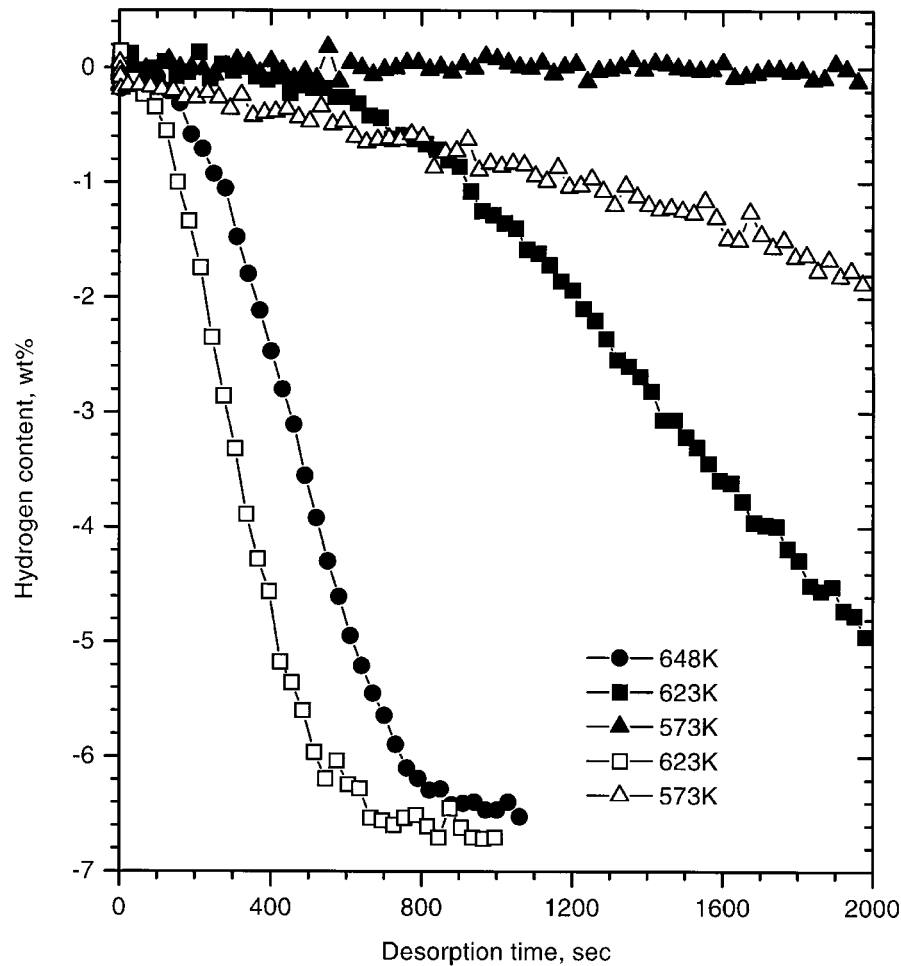


Fig. 3. Hydrogen desorption curves of unground  $MgH_2$  (filled marks) and ball-milled (hollow marks)  $MgH_2$  under a hydrogen pressure of 0.015 MPa.

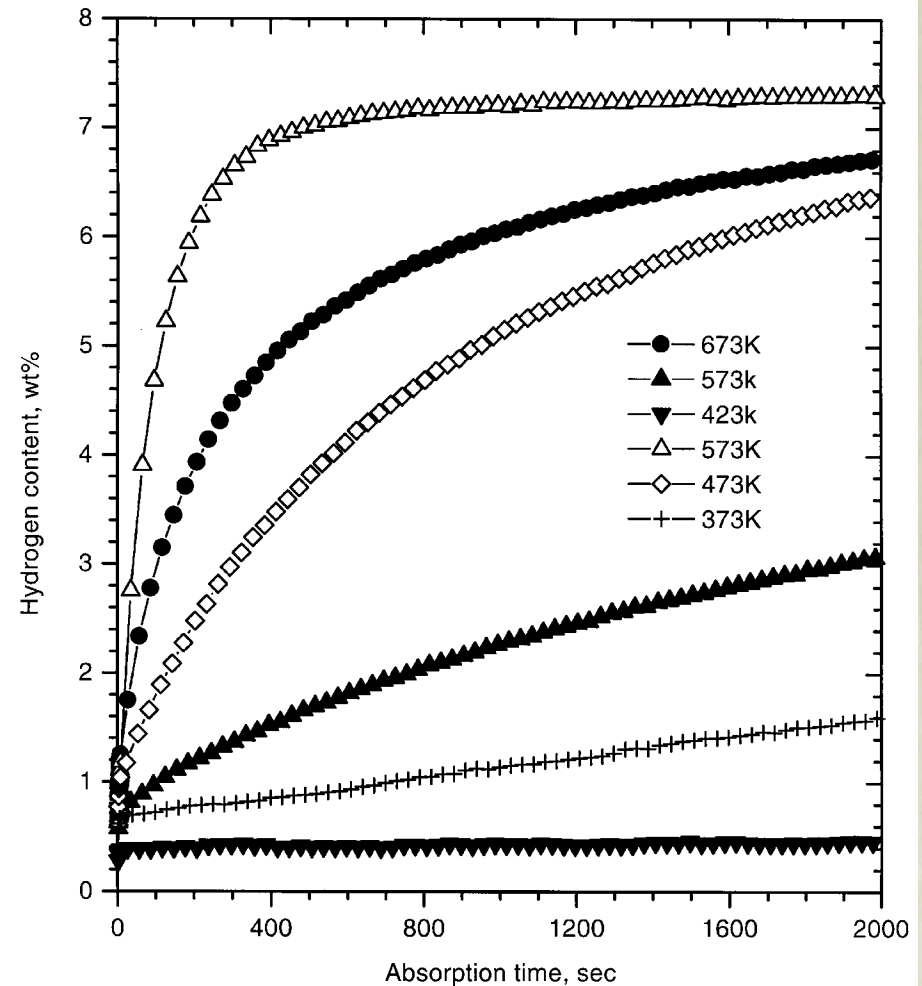


Fig. 4. Hydrogen absorption curves of the unground (filled marks) and ball-milled (hollow marks)  $MgH_2$  under a hydrogen pressure of 1.0 MPa.